Pattern Formation and Nanoscaled Structures in Thin Film Formation

Guest Editorial

This first twelve papers of this issue of Scanning Microscopy contains the refereed articles which were submitted in conjunction with the program on **Pattern Formation and Nanoscaled Structures in Thin Film Formation** held during the May 1996 Scanning Microscopy Meeting at Bethesda, Maryland.

The program addressed the status of research on fundamental and applied aspects of pattern formation related issues in thin film growth. The diversity of phenomena studied is illustrated by the scope and emphasis of the sessions including: surface and interface defect formation and structure, phase separation on surfaces and epitaxial growth modes, surface roughness, step formation and dynamics during growth, characterization techniques, with a focus on electron microscopy and tunneling methods, synthetic sublithographic nanostructures, and defect engineering and related applications for mismatched materials.

The refereeing process took place following the conference in order to ensure high standards for acceptance. We would like to acknowledge the timely and often painstaking efforts by all those involved as referees (see page 253).

The support, encouragement and financial assistance of several organizations is much appreciated, of these we wish to particularly mention Osaka University, the University of Maryland, the University of Western Ontario, the Centre for Chemical Physics in London, Ontario, and Scanning Microscopy International.

It is for the enthusiasm and appreciation of all the individuals who supported the 1996 program (contributors, attendees and sponsors) that we decided to organize a similar session during the Scanning Microscopy 1997 Meeting in Chicago (May 10-15) which is entitled **Formation and Properties of Nanoscaled Structures**. We hope for a similarly successful session with a strong participation from our research community.

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